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| APPLICATION NO. FILING DATE | | LING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. | |
|-----------------------------|------|---------------|---------------------------------|---------------------|------------------|--|
| 10/709,924 06/07/2004 | | 06/07/2004 | Jen-Yao Hsu | 13366-US-PA | 3923 | |
| 31561 | 7590 | 06/17/2005 | | EXAMINER | | |
| • | | TELLECTUAL PR | ERDEM, FAZLI | | | |
| 7 FLOOR-1. ROOSEVEL | • | SECTION 2 | ART UNIT PAPER NU | | | |
| • | 100 | | 2826 DATE MAILED: 06/17/2005 | | | |
| TAIWAN | | | | | | |

Please find below and/or attached an Office communication concerning this application or proceeding.

| | | Application | on No. | Applicant(s) | | | | | |
|--|--|--|---|--|--------|--|--|--|--|
| | | 10/709,9 | 24 | HSU, JEN-YAO | | | | | |
| Office Action Summary | | | | Art Unit | | | | | |
| | | Fazli Erde | :m | 2826 | | | | | |
| Period fo | The MAILING DATE of this communication a or Reply | ppears on the | cover sheet with the c | correspondence ad | Idress | | | | |
| THE - Exte after - If the - If NO - Failt Any | ORTENED STATUTORY PERIOD FOR REF MAILING DATE OF THIS COMMUNICATION nsions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a representation of the period for reply is specified above, the maximum statutory period reply within the set or extended period for reply will, by state reply received by the Office later than three months after the mailed patent term adjustment. See 37 CFR 1.704(b). | N. 1.136(a). In no even eply within the state od will apply and w ute, cause the app | ent, however, may a reply be tin utory minimum of thirty (30) day ill expire SIX (6) MONTHS from lication to become ABANDONE | nely filed s will be considered time the mailing date of this c D (35 U.S.C. § 133). | - T | | | | |
| Status | | | | | | | | | |
| 1)⊠ |)⊠ Responsive to communication(s) filed on <u>03 May 2005</u> . | | | | | | | | |
| 2a) <u></u> ☐ | ☐ This action is FINAL. 2b) ☐ This action is non-final. | | | | | | | | |
| 3)□ | Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. | | | | | | | | |
| Disposit | ion of Claims | | , | | | | | | |
| 5)□ 6)⊠ 7)⊠ | Claim(s) 1-6 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. Claim(s) is/are allowed. Claim(s) 1 and 4 is/are rejected. Claim(s) 2,3,5 and 6 is/are objected to. Claim(s) are subject to restriction and/or election requirement. | | | | | | | | |
| Applicat | ion Papers | | | | | | | | |
| 10) | The specification is objected to by the Exami The drawing(s) filed on is/are: a) are Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the | ccepted or b) ne drawing(s) bection is requir | pe held in abeyance. See ed if the drawing(s) is ob | e 37 CFR 1.85(a). jected to. See 37 C | • | | | | |
| Priority (| under 35 U.S.C. § 119 | | | | | | | | |
| 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. | | | | | | | | | |
| Attachmen | | | | | | | | | |
| 2) Notice No | ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/0 er No(s)/Mail Date | 98) | 4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other: | | O-152) | | | | |

DETAILED ACTION

Allowable Subject Matter

1. Claims 2, 3, 5 and 6 objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1 and 4 rejected under 35 U.S.C. 103(a) as being unpatentable over Liu et al. (6,265,752) in view of Liu (6,333,234) further in view of Chen (2005/0118768).

Regarding Claims 1 and 4, Liu et al. disclose a method of forming a HVNMOS with an N+ buried layer combined with a well and a structure of the same where in Fig. 5, it is disclose a substrate 20, a gate dielectric 28 on the substrate, gate 30, doped N+ doped regions serving as source/drain, FOX field isolation region 26 between the gate and doped regions. Liu et al. fail to disclose the required drift regions and the second doped region serving as modifying doped region. However, Liu discloses a method for making a HVMOS transistor where in Fig. 10-, drift regions 122 lie between field isolation region 108/109 and substrate 101. Futhermore, Chen discloses a method of forming high voltage metal oxide semiconductor transistor where in Fig. 12, second doped region 74 serving as modifying doped region is situated around first doped region 72.

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It would have been obvious to one of having ordinary skill in the art at the time the invention was made to include the required drift region and the second doped region around the first doped region in Liu et al. as taught by Liu and Chen respectively in order to have a semiconductor device with increased performance.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (571) 272-1914. The examiner can normally be reached on M - F 8:00 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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FE June 12, 2005